

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	58279	howard.inv. or (micron adj technology).as.	US-PGPUB; USPAT	OR	OFF	2007/02/05 12:03
L2	7244	1 and (insulative or insulating) and (organosilicon\$1 or silicon\$7 or (plasma adj polymerized adj methylsilane) or ppms or ppmso)	US-PGPUB; USPAT	OR	OFF	2007/02/05 12:07
L3	19	2 and (expos\$6 with radiation with (insulat\$4 or ppms or ppmso))	US-PGPUB; USPAT	OR	OFF	2007/02/05 12:09
L4	4	2 and (expos\$6 with radiation with (insulat\$4 or ppms or ppmso)) and (oxide with layer with (oxygen adj plasma))	US-PGPUB; USPAT	OR	OFF	2007/02/05 12:12
L5	134	((photo\$1definable or organosilicon\$1 or silicon\$7 or ppms or (plasma adj polymerized adj methylsilane)) with layer with expos\$6 with radiation).clm.	US-PGPUB; USPAT	OR	OFF	2007/02/05 12:16
L6	47	((photo\$1definable or organosilicon\$1 or silicon\$7 or ppms or (plasma adj polymerized adj methylsilane)) with layer with expos\$6 with radiation).clm.	US-PGPUB	OR	OFF	2007/02/05 12:16
L7	3	6 and (oxide with layer with oxygen with plasma).clm.	US-PGPUB	OR	OFF	2007/02/05 12:18
L8	146821	(photo adj definable adj layer) or (photo\$1definable adj layer) or ppms or (plasma adj polymerized adj methylsilane) or (silicon\$7 with layer) or (hard adj mask adj layer)	USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/02/05 12:22
L9	7307	8 same expos\$6 same remov\$6	USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/02/05 12:23
L10	14	8 same expos\$6 same remov\$6 same (oxide with (oxygen adj plasma))	USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/02/05 12:24

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L1	58279	howard.inv. or (micron adj technology).as.	US-PGPUB; USPAT	OR	OFF	2007/02/05 12:03
L2	7244	1 and (insulative or insulating) and (organosilicon\$1 or silicon\$7 or (plasma adj polymerized adj methylsilane) or ppms or ppmso)	US-PGPUB; USPAT	OR	OFF	2007/02/05 12:07
L3	19	2 and (expos\$6 with radiation with (insulat\$4 or ppms or ppmso))	US-PGPUB; USPAT	OR	OFF	2007/02/05 12:09
L4	4	2 and (expos\$6 with radiation with (insulat\$4 or ppms or ppmso)) and (oxide with layer with (oxygen adj plasma))	US-PGPUB; USPAT	OR	OFF	2007/02/05 12:12
L5	134	((photo\$1definable or organosilicon\$1 or silicon\$7 or ppms or (plasma adj polymerized adj methylsilane)) with layer with expos\$6 with radiation).clm.	US-PGPUB; USPAT	OR	OFF	2007/02/05 12:16
L6	47	((photo\$1definable or organosilicon\$1 or silicon\$7 or ppms or (plasma adj polymerized adj methylsilane)) with layer with expos\$6 with radiation).clm.	US-PGPUB	OR	OFF	2007/02/05 12:16
L7	3	6 and (oxide with layer with oxygen with plasma).clm.	US-PGPUB	OR	OFF	2007/02/05 12:18
L8	146821	(photo adj definable adj layer) or (photo\$1definable adj layer) or ppms or (plasma adj polymerized adj methylsilane) or (silicon\$7 with layer) or (hard adj mask adj layer)	USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/02/05 12:22
L9	7307	8 same expos\$6 same remov\$6	USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/02/05 12:23
L10	14	8 same expos\$6 same remov\$6 same (oxide with (oxygen adj plasma))	USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/02/05 12:42
L11	604022	semiconductor	US-PGPUB; USPAT	OR	OFF	2007/02/05 12:42
L12	50943	expos\$6 with (photo\$1definable or photosensitive or organosilicon\$1 or silicon\$7 or ppms or (plasma adj polymerized adj methylsilane)) with (layer or resist)	US-PGPUB; USPAT	OR	OFF	2007/02/05 12:47

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L13	6	12 same (remov\$5 with non\$1exposed) same (oxide with plasma)	US-PGPUB; USPAT	OR	OFF	2007/02/05 12:48
L14	110186	expos\$6 with (photo\$1definable or photosensitive or photoresist or resist or organosilicon\$1 or silicon\$7 or ppms or (plasma adj polymerized adj methylsilane)) with (layer or resist)	US-PGPUB; USPAT	OR	OFF	2007/02/05 12:48
L15	8	14 same (remov\$5 with non\$1exposed) same (oxide with plasma)	US-PGPUB; USPAT	OR	OFF	2007/02/05 12:48